

DEVICE AND METHOD OF CORRECTING EXPOSURE DEFECTS IN PHOTOLITHOGRAPHY

Abstract of the Disclosure

A corrective filter for use in an optical system to correct a defect in a reticle and/or pellicle. The corrective filter may be positioned between a light source and the reticle, between the reticle and a wafer, or in combination with the reticle and/or pellicle. The invention provides a method of characterizing the optical properties of the corrective filter.

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